L Number	Hits	Search Text	DB	Time stamp
1	244	(430/328.ccls. and (heat\$3 or bak\$3) same	USPAT;	2004/04/09 19:20
		(expos\$3) same (develop\$3)) not	US-PGPUB;	
		(((430/314,316,319-320,328-329).ccls. and	EPO; JPO;	
		((oxygen or "O.sub.2") same ((nitrogen or	IBM_TDB	
		"N.sub.2") and (hydrogen or "H.sub.2"))		
		same (ash\$3 or etch\$3))) and (heat\$3 or		
		bak\$3) same (resist or photoresist))		
2	33		USPAT;	2004/04/09 19:26
		((oxygen or "O.sub.2") same ((nitrogen or	US-PGPUB;	
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
		same (ash\$3 or etch\$3))) and (heat\$3 or	IBM_TDB	
		bak\$3) same (resist or photoresist)		
3	3	((resist or photoresist) and	USPAT;	2004/04/09 19:28
		(napthoquinonediazide or	US-PGPUB;	
		napthoquinonediazido)) and (novolac or	EPO; JPO;	
		novolak) and dissolution near3 accelerat\$3	IBM_TDB	0004/04/00 10:00
4	55	· · · · · · · · · · · · · · · · · · ·	USPAT;	2004/04/09 19:28
		(napthoquinonediazide or	US-PGPUB;	
		napthoquinonediazido)	EPO; JPO;	
		////	IBM_TDB	2004/04/09 19:29
5	4	(((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:29
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) not (((((magnetic adj head)		
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and		
400		(polymethylglutarimide)		

			ri via a a a	000101000000000000000000000000000000000
6	31	(((((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:31
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		<pre>photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and</pre>	IBM_TDB	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		
		imag\$3 or pattern\$3))) and ((heat\$3 or		
		bak\$3) with (resist or photoresist or		
7	33	imag\$3 or pattern\$3)) ((430/314,316,319-320,328-329).ccls. and	USPAT;	2004/04/09 19:37
/	33	((oxygen or "O.sub.2") same ((nitrogen or	US-PGPUB;	2004/04/05 15.37
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
		same (ash\$3 or etch\$3))) and (heat\$3 or	IBM TDB	
		bak\$3) same (resist or photoresist)		
8	0	(((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:48
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or</pre>		
		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (napthoquinonediazide or		
		napthoquinonediazide of napthoquinonediazido)		
	1	Top one daring and a second	<u> </u>	

9	4	(((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:	: 55
		resistive) or magnetoresistive or	US-PGPUB;		
		magnetophotoresistive or (magneto adj	EPO; JPO;		
		photoresistive) or (giant adj magneto\$15)	IBM TDB	į	
		or (GMR same magneto\$15)).ti,ab.) and	_		
		(resist or photoresist or photopolymer\$7			
		or photoimag\$5)) and ((ash\$3 or (ash adj			
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3			
		or shrunk\$3 or contract\$3 or small\$3 or			
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4			
		or trim\$4 or less\$5 or tight\$4) same			
		(resist or photoresist or imag\$3 or			
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>			
		or (magneto adj resistive) or			
		magnetoresistive or magnetophotoresistive			
		or (magneto adj photoresistive) or (giant			
		adj magneto\$15) or (GMR same			
		magneto\$15)).ti,ab.) and (resist or			
		photoresist or photopolymer\$7 or			
		photoimag\$5)) and ((ash\$3 or (ash adj			
ĺ		treat\$4) or etch\$3 or narrow\$3 or shrink\$3			
		or shrunk\$3 or contract\$3 or small\$3 or			
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4			
		or trim\$4 or less\$5 or tight\$4) same			
		(resist or photoresist or imag\$3 or			
		<pre>pattern\$3))) and ((resist or photoresist</pre>			
		or imag\$3 or pattern\$3) same ((oxygen or			
		"O" or "O.sub.2") and (fluorine or			
		fluoride or "F" or "F.sub.2" or ((nitrogen			
		or "N" or "N.sub.2") and (hydrogen or "H"			
		or "H.sub.2")))))) and			
		(polymethylglutarimide)	-		

10	1 1	((((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:58
10	11	resistive) or magnetoresistive or	US-PGPUB;	2004/04/09 19:58
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	_	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
]		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
ĺ		or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or		1
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) not ((((((magnetic adj		
		head) or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
İ		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		
11	2.1	<pre>imag\$3 or pattern\$3)))</pre>		0004/04/00 00 00
11	31	(((((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 20:08
		resistive) or magnetoresistive or magnetophotoresistive or (magneto adj	US-PGPUB;	
		photoresistive) or (giant adj magneto\$15)	EPO; JPO; IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same	X .	
ĺ		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		
		imag\$3 or pattern\$3))) and ((heat\$3 or		
		bak\$3) with (resist or photoresist or		
		<pre>imag\$3 or pattern\$3))</pre>		
		1	l	

[-	22	(("20020042029") or ("6040965") or	USPAT;	2003/03/18 16:46
	22	("5932396") or ("6480355") or ("5747198")	US-PGPUB	2003/03/10 10:40
		or ("6289578") or ("5725997") or	00 10102	
		("6483664") or ("6501618") or ("6504678")		
		or ("20010010885") or ("20010019036") or		
		("20010027029") or ("6465149") or		
		("20010019465") or ("20010035355") or		
		("2001003465") or ("20010035343") or		1
		("20020037476") or ("20020071211") or		
		("20030007295") or ("20020187430")).PN.		
_	61373	((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 17:59
	013/3	resistive) or magnetoresistive or	US-PGPUB;	2003/03/07 17:33
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.	TDIA_TDB	
_	2793	(((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 18:00
-	2755	resistive) or magnetoresistive or	US-PGPUB;	2003/03/07 10:00
		magnetophotoresistive or (magneto adj	EPO; JPO;	
	İ	photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	1011-100	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)		
_	2003	((((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 19:27
	2003	resistive) or magnetoresistive or	US-PGPUB;	2003/03/07 13:27
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	TBM_TBB	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3	1	
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))		
_	65	(((((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 19:04
		resistive) or magnetoresistive or	US-PGPUB;	2003/03/07 13:04
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	1511_155	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
	1	or "H.sub.2")))))		

	00	(((((((magnetic adj head) or (magneto adj	HCDAT.	2004/04/09 20:07
_	23	' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' '	USPAT;	2004/04/09 20:07
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3	•	
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		-
		imag\$3 or pattern\$3))) and ((heat\$3 or		
		bak\$3) with (resist or photoresist or		
	5.0	imag\$3 or pattern\$3))	HODE TO	2002/02/07 10 00
_	56	((((((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 19:02
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4		÷
	*			
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
•		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
1		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		
		imag\$3 or pattern\$3))		
1	1	Imagyo or paccernyo//		1

- 33	((((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 20:06
	resistive) or magnetoresistive or	US-PGPUB;	
	magnetophotoresistive or (magneto adj	EPO; JPO;	
	photoresistive) or (giant adj magneto\$15)	IBM_TDB	
	or (GMR same magneto\$15)).ti,ab.) and		
	(resist or photoresist or photopolymer\$7		
	or photoimag\$5)) and ((ash\$3 or (ash adj		
	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
	or shrunk\$3 or contract\$3 or small\$3 or		
	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
	or trim\$4 or less\$5 or tight\$4) same		
	(resist or photoresist or imag\$3 or		
	pattern\$3))) and ((resist or photoresist		
	or imag\$3 or pattern\$3) same ((oxygen or		
	"O" or "O.sub.2") and (fluorine or	1	
	fluoride or "F" or "F.sub.2" or ((nitrogen		
	or "N" or "N.sub.2") and (hydrogen or "H"		
	or "H.sub.2")))))) and (((mill\$3 or ion		
	adj beam or FIB or RIE or ion adj etch\$3		
	or sputter\$3) or (lift adj off or liftoff		
	or remov\$3 or etchback or etch\$3 adj		
	back)) near5 (resist or photoresist or		
	imag\$3 or pattern\$3))) not		
	(((((((magnetic adj head) or (magneto adj		
	resistive) or magnetoresistive or		
	magnetophotoresistive or (magneto adj		
	photoresistive) or (giant adj magneto\$15)		
	or (GMR same magneto\$15)).ti,ab.) and		
	(resist or photoresist or photopolymer\$7		
	or photoimag\$5)) and ((ash\$3 or (ash adj		
	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
	or shrunk\$3 or contract\$3 or small\$3 or		
	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
	or trim\$4 or less\$5 or tight\$4) same		
	(resist or photoresist or imag\$3 or		
	pattern\$3))) and ((resist or photoresist		
	or imag\$3 or pattern\$3) same ((oxygen or		
	"O" or "O.sub.2") and (fluorine or		
	fluoride or "F" or "F.sub.2" or ((nitrogen		
	or "N" or "N.sub.2") and (hydrogen or "H"		
	or "H.sub.2")))))) and (((mill\$3 or ion		
	adj beam or FIB or RIE or ion adj etch\$3		
	or sputter\$3) or (lift adj off or liftoff		
	1 1 1		
	or remov\$3 or etchback or etch\$3 adj		
	back)) near5 (resist or photoresist or		1
	imag\$3 or pattern\$3))) and ((heat\$3 or		
	bak\$3) with (resist or photoresist or		
	imag\$3 or pattern\$3)))	L	

9	(((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:57
	resistive) or magnetoresistive or	US-PGPUB;	
	magnetophotoresistive or (magneto adj	EPO; JPO;	
	photoresistive) or (giant adj magneto\$15)	IBM TDB	
	or (GMR same magneto\$15)).ti,ab.) and		
	(resist or photoresist or photopolymer\$7		
	or photoimag\$5)) and ((ash\$3 or (ash adj		
	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
1 111	or shrunk\$3 or contract\$3 or small\$3 or		
	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
	or trim\$4 or less\$5 or tight\$4) same		
	(resist or photoresist or imag\$3 or		
	pattern\$3))) and ((resist or photoresist		
	or imag\$3 or pattern\$3) same ((oxygen or		
	"O" or "O.sub.2") and (fluorine or		
	fluoride or "F" or "F.sub.2" or ((nitrogen		
	or "N" or "N.sub.2") and (hydrogen or "H"		
	or "H.sub.2")))))) not ((((((magnetic adj		
	head) or (magneto adj resistive) or		
	magnetoresistive or magnetophotoresistive		
	or (magneto adj photoresistive) or (giant		
	adj magneto\$15) or (GMR same		
1 11/2	magneto\$15)).ti,ab.) and (resist or		
	photoresist or photopolymer\$7 or		
	photoimag\$5)) and ((ash\$3 or (ash adj		
	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
	or shrunk\$3 or contract\$3 or small\$3 or		*
	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
	or trim\$4 or less\$5 or tight\$4) same		
	(resist or photoresist or imag\$3 or		
	pattern\$3))) and ((resist or photoresist		
	or imag\$3 or pattern\$3) same ((oxygen or		
	"O" or "O.sub.2") and (fluorine or		
	fluoride or "F" or "F.sub.2" or ((nitrogen		
	or "N" or "N.sub.2") and (hydrogen or "H"		
	or "H.sub.2")))))) and (((mill\$3 or ion		
	adj beam or FIB or RIE or ion adj etch\$3		
*	or sputter\$3) or (lift adj off or liftoff		
	or remov\$3 or etchback or etch\$3 adj		
	back)) near5 (resist or photoresist or		
	imag\$3 or pattern\$3)))	1	

_	1938	(((((magnetic adj head) or (magneto adj	USPAT;	2003/03/18 16:14
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>		
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2"))))))		
_	1	("5872693").PN.	USPAT;	2003/03/08 15:24
			US-PGPUB	0004/04/00 10 54
-	2	(((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:54
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15)	EPO; JPO; IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	1011-100	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>		
		or (magneto adj resistive) or		
'		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same		
		magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) and ((resist or photoresist</pre>		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (polymethylglutarimide)		
	,	(boramernathratumme)	I	1

USPAT: USPAT:					
magnetophotocresistive or (magneto adj photoresistive) or (gint adj magnetos15) IBM_TDB	_	0	((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:47
photocresistive or (qiant adj magneto\$15) or (GMR same magneto\$15); bit, ab.) and (resist or photomags5); and (Gashās or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 same (resist or photocresist) or magneto adj resist(ve) or magneto adj resist(ve) or magneto adj resist(ve) or magnetosit(), ti, ab.) and (resist or photoresist) or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or photoresist or narrow\$3 or shrink\$3 or shrink			resistive) or magnetoresistive or	US-PGPUB;	
photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15). vit, ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5) and ((ash\$3) or (ash add) treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or	1			EPO; JPO;	
or (GMR same magnetosis). ti,ab.) and (resist or photoresist or photopolymers? or photoimag53)) and ((ash\$3 or (ash ad) treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or roducat\$3 or decreas\$3 or \$1im\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3])) not ((((mempetic adj had) magnetosis))) not ((((mempetic adj had) magnetosis)) or (GMR same nagnetosis)) or (GMR same nagnetosis)) or (GMR same nagnetosis)) ind ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$2 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or recuts3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4; same (resist or photoresist or imag\$3 or pattern\$3])) and ((resist or photorsis) or pattern\$3])) and ((resist or photorsis) or pattern\$3])) and ((resist or photorsis) or pattern\$3])) and ((resist or photorsis) or imag\$3 or pattern\$3; same (resist or photoresist) and or imag\$3 or pattern\$3, same (loxygen or "O" or "0.sub.2") and (hydrogen or "H" or "II.sub.2"))))) and ((napthoquinonediazide) 1 ((resist or photoresist) and (napthoquinonediazide) 2 ((resist or photoresist) and (napthoquinonediazide) 3 ((resist or photoresist) and (napthoquinonediazide) 4 ((resist or photoresist) 0 ((ad30/314,316,319-320,328-329).ccls. and (napthoquinonediazide) 1 ((ad30/314,316,319-320,328-329).ccls. and (nowygen or "0.sub.2") same (initropen or "N. sub.2") and (hydrogen or "H. sub.2")) same (ash\$3 or bak\$3) same (oxpos\$3) same (develop\$3) 2 ((ad30/314,316,319-320,328-329).ccls. and (nowygen or "0.sub.2") same (initropen or "N. sub.2") and (hydrogen or "H. sub.2")) same (ash\$3 or bak\$3) same (oxpos\$3) same (develop\$3) 2 ((ad30/314,316,319-320,328-329).ccls. and (nowygen or "0.sub.2") same (initropen or "N. sub.2") same (ash\$3 or bak\$3) same (oxpos\$3) same (develop\$3) 2 ((ad30/314,316,319-320,328-329).ccls. and (nowygen or "0.sub.2") same (initropen or "N. sub.2") same (ash\$3 or chis\$3); bid (heat\$3 or bak\$3) same (oxpos\$3) same (fevelop\$3) 2 ((ad30/314,316,319-320			photoresistive) or (giant adj magneto\$15)	IBM TDB	
(resist or photoreaist or photoplymers7 or photoimag53) and (lash83 or (ash add) treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or lill\$3 or reduc\$3 or narrow\$3 or shrink\$3 or lill\$3 or reduc\$3 or decreas\$3 or shink\$4 or trins6 or leash\$5 or thin\$4 same (resist or photoreaist) or analysis or shink\$4 or trins6 or leash\$5 or thin\$4 same (resist or photoreaist) or analysis or analysis or analysis or analysis or analysis or analysis or analysis or shrink\$3 or sh			or (GMR same magneto\$15)).ti,ab.) and		
or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same ((resist or photoresist) or imag\$3 or pattern\$3))) not ((((((ingnetic adj head) or (magneto adj resist.ve) or magnetoresistive or magnetosistive or magneto) or (qiant adj magneto\$15) or (GR same magneto\$15), ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist) or imag\$5 or pattern\$3) same ((axygen or "O" or "O.sub.2") and (fluorine or fluoride or "" or "" and." and." or "Insub.2"))))) and ((resist or photoresist) and ((napthequinonediazide) ((resist or photoresist) and ((napthequinonediazide) ((resist or photoresist)) and ((resist or photoresist)) - 3 ((resist or photoresist)) - 5 ("422412" "4/45042" "5525631" "50, JPO; namphoquinonediazide) ((resist or photoresist)) - 6 (430/314,18,319-320,288-329),ccls. and ((resist or or or sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2") same (ash\$3 or etch\$3)) - 7 ("30/328,ccls. and (heat\$3 or bak\$3) same (expos\$3) same (resist or photoresist) - 8 (430/314,519-320,328-329),ccls. and ((respos\$3) same (develop\$3)) - 8 (2003/03/10 17:38 - 9 (2003/03/10 17:38 -			(resist or photoresist or photopolymer\$7		
treats4) or etch53 or nairow33 or shrinks3 or shrunk33 or contracts3 or small30 or littl33 or reduce3 or small30 or littl33 or reduce3 or decreas3 or slims4 or trim84 or less55 or tight54) same (resist or photoresist or imag51 or pattern531) not (((((magnetic ad) head) or (magneto ad) resistive) or (magneto ad) reduced or (magneto ad) photoresistive or magnetore) not (((magnetic ad) head) or (magneto ad) photoresistive) or (glant ad) magnetof51) it; ab) and summisted or photoresistive or magnetore) and (magneto ad) should be added to the state of the state			or photoimag\$5)) and ((ash\$3 or (ash adi		
or shrunk3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or less\$5 or tight\$4] same (resist or photoresist or imag\$5 or pattern\$3])) not (((((((((((((((((((((((((((((((((((treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
littl33 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or leas\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$31) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magnetophotoresistive or pattern\$31) not (((((magnetic adj head) or (magneto\$15)) or (CMR same magneto\$15)) .i.,sb.) and (resist or photoresist or photoresist or photoresist or photoresist or magneto\$15) and ((ash\$3 or sah adj treath) and ((ash\$3 or trim\$4) and ((ash\$3 or sah adj treath) and ((ash\$3 or sah adj treat			or shrunk\$3 or contract\$3 or small\$3 or		
crrim44 or less50 or tight44 same (resist or photoresist or imaga5 or pattern53)) not ((((((magnetic adj head) or (magnetoadj resistive) or magnetoadj resistive) or (giant adj magneto515) or (GMR same magneto515) or (GMR same magneto515) or (GMR same magneto515) or (GMR same magneto515) or (GMR same magneto515) or (GMR same resist or photoresist) or photoresist or photoresist or shrunk3) or shrunk3) or shrunk3) or shrunk3 or or shrunk3) or shrunk3) or or contract3 or small3 or litt133 or reduc3 or decreas3 or salm34 or trim44 or t					
(resist or photoresist or imag\$3 or magnetors) not ((((((magnetic ad) head) or (magneto ad) resistive) or magnetorsistive or magnetophotoresistive or (giant ad) magnetof5]) or (GMR same magnetof5]). (in, ab.) and (resist or photopolymer\$7 or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash ad) treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrink\$3 or shrink\$3 or or shrink\$3 or or shrink\$3 or or photoresist or imag\$3 or slin\$4 or Lrim\$4 or less\$5 or tight\$4] same (resist or photoresist or imag\$3 or pattern\$3])) and ((resist or photoresist or imag\$3 or pattern\$3]) and ((resist or photoresist or imag\$3 or pattern\$3])) and ((resist or photoresist or imag\$3 or pattern\$3])) and ((resist or photoresist) or imag\$3 or pattern\$3])) and ((napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide)) and (napthoquinonediazide or napthoquinonediazide)) and (napthoquinonediazide) and (napthoquinonediazide) and (napthoquinonediazide) and (napthoquinonediazide) and (napthoquinonediazide) and (novolac or napthoquinonediazide) and (novolac or novolac)					
pattern\$31)] not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive) or magnetoresistive) or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti, ab.) and (resist or photoresist or photopolymer\$7 or photoresist or photopolymer\$7 or photoresist or photopolymer\$7 or photoresist or or shrunk\$3 or shrunk\$3 or shrunk\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slin\$4 or trim\$4 or less\$5 or tight\$4\] same (resist or photoresist or imag\$3 or pattern\$31) and ((resist or photoresist or imag\$3 or pattern\$31) ame ((rosist or photoresist or imag\$3 or pattern\$31) ame ((rosist or photoresist) and (napthoquinonediazide) or "N" or "N" sub.2") and (hydrogen or "H" or "H. sub.2")))))) and ((napthoquinonediazide) raphtoquinonediazide or napthoquinonediazide) raphtoquinonediazide or napthoquinonediazide) raphtoquinonediazide) raphtoquinonediazide) raphtoquinonediazide or napthoquinonediazide or napthoquinonediaz					
or (magneto adj resistive) or magnetoresistive or (magneto adj photoresistive) or (giant adj magnetofs) or (GMR same magnetofs)). ci, ab.) and (resist or photoresist) or photoresistive) or photoresistive or photoresistive or photoresistive or photoresistion or photoresistive) or photoresistive or photoresistive or photoresistive or photoresistive or photoresistive or imags3 or cettofs3 or narrows3 or shrink\$3 or shrink\$3 or shrink\$3 or shrink\$4 or trim\$4 or less\$5 or tight\$4] same (resist or photoresist or imag\$3 or pattern\$3])) and ((resist or photoresist or imag\$3 or pattern\$3])) and ((resist or photoresist or imag\$3 or pattern\$3])) and ((resist or photoresist or imag\$3 or pattern\$3]))) and (magthoquinonediazide or napthoquinonediazide or					
magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (magneto adj photoresistive) or (giant adj magnetos[5]). Ti, ab.) and (reaist or photoresist or photopolymers? or photoresist or photopolymers? or photoresist or photopolymers? or photoresist or photopolymers? or shrinks? or shrinks? or shrinks? or shrinks? or shrinks? or trims4 or trims4 or trims4 or trims4 or trims4 or trims4 or or trims4 or patterns[3]) and (casts or photoresist or imags? or patterns[3]) and (fluorine or fluoride or "F" or "F.sub.2" or (fnitrogen or "M" or "M.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (mapthoquinonediazide) - [3] ((resist or photoresist) and (mapthoquinonediazide)					
or (magneto adj photoresistive) or (qiant adj magneto\$15) or (CMR same magneto\$15) or (CMR same magneto\$15) or (CMR same magneto\$15) or (CMR same photoresist or photoplymer\$7 or photofinag\$5) and ((ash\$3 or (ash adj treat\$4) or strunk\$3 or contract\$3 or small\$3 or shrunk\$3 or shrunk\$3 or shrunk\$3 or shrunk\$3 or contract\$3 or small\$3 or litt183 or reduc\$3 or decreas\$3 or slin84 or trin\$4 or less\$5 or tight\$4\) same (tresist or photoresist or imag\$3 or pattern\$3\)) and ((resist or photoresist or inag\$3 or pattern\$3\)) and ((swygen or "0" or "N.sub.2") and (fluorine or fluoride or "8" or "N.sub.2") and (hydrogen or "H" or "N.sub.2") and (napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide) ((resist or photoresist) and (napthoquinonediazide) (resist or photoresist) and (napthoquinonediazide) (resist or photoresist) and (lowgen or "8.sub.2") same (sans) are (lawyen or "8.sub.2") same ((lowgen or "8.sub.2") same (resist or photoresist) ((lay0.314,316,319-320,328-329).cls. and (lowgen or "8.sub.2") same (lowgen or "8.sub.2			magnetoresistive or magnetophotoresistive		
adj magneto\$15).ti,ab. and (resist or photoresist) or photoimag\$5) and (sah\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrink\$3 or otheret\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trin\$4 or less\$5 or tight\$4] same (resist or photoresist or imag\$3 or pattern\$3)) and (fluersist or photoresist or imag\$3 or pattern\$3)) and (fluersist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" o" "O.sub.2") and (fluorine or fluoride or "F" or "F. sub.2" or (initrogen or "H. sub.2")) and (napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or nevolak) and dissolution near3 accelerat\$3 ("4524121" "4745042" "5252831" USPAT, US-PCPUB; EPO; JPO; IRM TDB ((oxygen or "N. sub.2") and (hydrogen or "H. sub.2") same (ash\$3) or etch\$3) clintrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (ash\$3 or etch\$3) clintrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (ash\$3) same (resist or photoresist) and (lasy3) same (resist or photoresist) and (last3) or bak\$3) same (resist or photoresist) and (last3) or bak\$3) same (resist or photoresist) and (last3) or bak\$3) same (lattrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (lattrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (lattrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (lattrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (lattrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (lattrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (lattrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (lattrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (lattrogen or "N. sub.2") and (hydrogen or "H. sub.2") same (lattrogen or "N. sub.2") same (lattr			or (magnete add photoresistive) or (might		
magmeto\$15)).ti,ab.) and (resist or photore)ymer\$7 or photoreniacy for photoreplymer\$7 or photorimag\$5)) and ((aab\\$3 or (ash adj treat\\$4) or etch\\$3 or marrow\\$3 or shrink\\$3 or arrow\\$3 or shrink\\$3 or or shrink\\$3 or or shrink\\$3 or or shrink\\$3 or or shrink\\$3 or or shrink\\$3 or or shrink\\$3 or or shrink\\$3 or small\\$3 or shrink\\$3 or or shrink\\$3 or or shrink\\$3 or or shrink\\$3 or small\\$3 or shrink\\$3 or or shrink\\$3 or small\\$3 or shrink\\$3 or shri					
photoresist or photopolymer\$7 or photoimags\$5) and (ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrink\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "0" or "N.sub.2") and (hydrogen or "H" or "H.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (napthoquinonediazide or napthoquinonediazide and (novolac or novolak) and dissolution near3 accelerat\$3 "5604073" "\$600403" "\$5252831" "5604073" "\$600403" "\$5252831" "5604073" "\$600403" "\$5252831" "5604073" "\$600403" "\$600403" "\$500403" "\$500403" "\$60					
photoimag\$5) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrows3 or shrink\$3 or shrunk\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or """ or "".sub.2") and (hydrogen or "H" or "H. sub.2"))))) and (napthoquinonediazide or napthoquinonediazide or napthoquinonediazido)					
treat\$41 or etch\$3 or narrow\$3 or shrink\$3 or shrink\$3 or or shrink\$3 or contract\$3 or samil\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$41 same (resist or photoresist or imag\$3 or pattern\$31) and ((resist or photoresist or imag\$3 or pattern\$31) and ((resist or photoresist or imag\$3 or pattern\$31) and ((rowpen or "0" or "0. sub.2") and (fluorine or fluoride or "F" or "F. sub.2" or ((nitrogen or "N" or "N. sub.2"))))) and (napthoquinonediazide) or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide or novolak) and dissolution near3 accelerat\$3 IBM TOB USPAT (4504073" "5800963").FN. 455 ("4524121" "4745042" "552831" USPAT (USPAT (USPAT)				-	
or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4] same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "(" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2"))))) and (napthoquinonediazide or napthoquinonediazide or napthoquinonediazido) - 3 ((resist or photoresist) and (napthoquinonediazido) napthoquinonediazido) - 3 ((resist or photoresist) and (napthoquinonediazido) napthoquinonediazido) napthoquinonediazido) - 4 ((resist or photoresist) and (napthoquinonediazido) napthoquinonediazido) napthoquinonediazido) - 5 ("452421" "4744042" "5525283" "5604073" "5800963").FN. - 4 (30(314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3)) same (ash\$3 or etch\$3)) same (ash\$3 or etch\$3)) and (heat\$3 or ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3)) and (neat\$3 or ((axygen or "O.sub.2") same ((nitrogen or "N.sub.2") same ((nitrogen or "N.sub.2") same ((sah\$3) or etch\$3)) and ((cxygen or "O.sub.2") same ((nitrogen or "N.sub.2") same ((sah\$3)) and ((cxygen or "O.sub.2") same ((nitrogen or "N.sub.2") same ((sah\$3)) same (expos\$3) same (develop\$3) not (((xygen or "O.sub.2") same ((nitrogen or "N.sub.2") same ((sah\$3) or etch\$3)) same (ash\$3 or etch\$3)) and ((cxygen or "O.sub.2") same ((nitrogen or "N.sub.2") same ((sah\$3) or etch\$3)) same (ash\$3 or etch\$3)) and ((cxygen or "O.sub.2") same ((nitrogen or "N.sub.2") same (sah\$3 or etch\$3)) same (ash\$3 or etch\$3)) and ((saygen or "O.sub.2") same ((saygen or "O.sub.2") same ((saygen or "O.sub.2") same ((saygen or "O.sub.2") same ((saygen or "O.sub.2")) same (ash\$3 or etch\$3)) and ((saygen or "O.sub.2") same (saygen or "O.sub.2") same (saygen or "O.sub.2") same (saygen or "O.sub.2") same (ash\$3 or etch\$3)) and (saygen or "O.sub.2") same (ash\$3 or etch\$3)			tractéd or atabés or parrows or shrinks		
Dittl\$3 or reduc\$3 or decreas\$3 or slim\$4 or ltsim\$4 or ltsim\$5 or imaq\$3 or pattern\$3] and ((resist or photoresist or imaq\$3 or pattern\$3] same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2") or ((nitrogen or "N" or "N.sub.2") and (fluorine or fluoride or "F" or "F.sub.2") or ((nitrogen or "N" or "N.sub.2")) and ((napthoquinonediazide) ((resist or photoresist) and ((napthoquinonediazide) (napthoquinonediazide) or napthoquinonediazide) or napthoquinonediazide) or napthoquinonediazide) or napthoquinonediazide) and (novolac or napthoquinonediazide) or novolak) and dissolution near3 accelerat\$3 USPAT; US-PCPUB; EPO; JPO; IBM TDB ((vasyen or "O. sub.2") same ((nitrogen or "M.sub.2") = "56004073" "5600963").FN. 45 (430/314,316,319-320,328-329).ccls. and ((oxygen or "O. sub.2") same ((nitrogen or "N. sub.2") and (hydrogen or "H. sub.2") Same (ash\$3 or etch\$3)) and (heat\$3 or bak\$3) same (resist or photoresist) (303/03/10 17:38 (expos\$3)) same (develop\$3) not ((430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not ((430/314,316,319-320,328-329).ccls, and ((oxygen or "O. sub.2") same (ash\$3 or etch\$3)) and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3) not ((430/314,316,319-320,328-329).ccls, and ((oxygen or "O. sub.2") same (ash\$3 or etch\$3)) same (as					
cr trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3)) same ((oxygen or "0" or "0" or "N".sub.2"))))) and ((napthoquinonediazide or napthoquinonediazide) (resist or photoresist) and (napthoquinonediazide) or napthoquinonediazide or napthoquinonediazide or napthoquinonediazide) or napthoquinonediazide or napthoquinonediazide) and (novolac or novolak) and dissolution near3 accelerat\$3 (researchino or novolak) and dissolution near3 accelerat\$3 (researchino or novolak) and dissolution near3 accelerat\$3 (researchino or novolak) and dissolution near3 accelerat\$3 (researchino or novolak) and dissolution near3 accelerat\$3 (researchino or novolak) and dissolution near3 accelerat\$3 (researchino or novolak) and dissolution near3 accelerat\$3 (researchino or novolak) and dissolution near3 accelerat\$3 (researchino or novolak) and dispatchino or novolak) and researchino or novolak) and novolac or novolak) and researchino or novolak) and dispatchino or novolak) and dispa					
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or imag\$3 or pattern\$3] same ((loxygen or "0" or "0.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))) and (napthoquinonediazide) and (napthoquinonediazide) apthoquinonediazide) and (napthoquinonediazide) and (napthoquinonediazide) and (napthoquinonediazide) and (napthoquinonediazide) and (novolac or napthoquinonediazide) and (novolac					
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fluoride or "F" or "F. sub.2") and (hydrogen or "H" or "N. sub.2") and (hydrogen or "H" or "B. sub.2"))))) and (napthoquinonediazide or napthoquinonediazide) - 51 (resist or photoresist) and (napthoquinonediazide) - 3 ((resist or photoresist) and (napthoquinonediazide) - 3 ((resist or photoresist) and (napthoquinonediazide) - 3 ((resist or photoresist) and (napthoquinonediazide) and (novolac or napthoquinonediazide)) and (novolac or novolak) and dissolution near3 accelerat\$3 - 5 ("4524121" "4745042" "5252831" "5604073" "5800963"). FN. - 45 (430/314, 316, 319-320, 328-329).ccls. and ((oxygen or "O. sub.2") same ((nitrogen or "N. sub.2")) asame (ash\$3 or etch\$3)) - 25 ((430/314, 316, 319-320, 328-329).ccls. and ((oxygen or "O. sub.2") same ((nitrogen or "N. sub.2")) and (hydrogen or "H. sub.2")) - 3 ((430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (resist or photoresist) - 216 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not ((430/314, 316, 319-320, 328-329).ccls. and ((oxygen or "O. sub.2")) same (and (heat\$3 or bak\$3) same (expos\$3) same (fexpos\$3) sa					
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napthoquinonediazido (resist or photoresist) and (napthoquinonediazide or napthoquinonediazide or					
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napthoquinonediazido EPO; JPO; IBM_TDB USPĀT; US-PGPUB; EPO; JPO; napthoquinonediazide or napthoquinonediazide or napthoquinonediazido) and (novolac or napthoquinonediazido) nad (novolac or napthoquinonediazido) IBM_TDB USPĀT	_	31			2003/03/03 13:20
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Comparison of the property o			napenoquinonearabras,		
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napthoquinonediazido)) and (novolac or novolak) and dissolution near3 accelerat\$3 ("4524121" "4745042" "5522831" USPĀT 2003/03/10 09:27 "5604073" "5800963").PN. 45 (430/314,316,319-320,328-329).ccls. and ((oxygen or "0.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3)) 25 ((430/314,316,319-320,328-329).ccls. and ((oxygen or "0.sub.2") same ((nitrogen or "N.sub.2")) same (ash\$3 or etch\$3)) and (heat\$3 or bak\$3) same (resist or photoresist) 216 430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3) ((430/314,316,319-320,328-329).ccls. and (USPAT; US-PGPUB; EPO; JPO; IBM_TDB (USPAT; US-PGPUB; EPO; JPO; IBM_TDB (USPAT; US-PGPUB; EPO; JPO; IBM_TDB (USPAT; US-PGPUB; EPO; JPO; IBM_TDB (USPAT; US-PGPUB; EPO; JPO; IBM_TDB ((430/314,316,319-320,328-329).ccls. and ((oxygen or "0.sub.2") same ((nitrogen or "N.sub.2")) same (ash\$3 or etch\$3)) and (heat\$3 or bak\$3) same (SPPOUB; EPO; JPO; IBM_TDB (USPAT; US-PGPUB; I	-	,		· ·	
novolak and dissolution near3 accelerat\$3 IBM TDB ("4524121" "4745042" "5252831" "5604073" "5800963").PN. 45					
- 5 ("4524121" "4745042" "5252831" "50004073" "5800963"). PN 45 (430/314,316,319-320,328-329).ccls. and ((oxygen or "0.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3)) - 25 ((430/314,316,319-320,328-329).ccls. and ((oxygen or "0.sub.2") same ((nitrogen or "N.sub.2")) same (ash\$3 or etch\$3)) and (hydrogen or "H.sub.2")) same (ash\$3) same (resist or photoresist) - 216 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3) - 211 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not ((430/314,316,319-320,328-329).ccls. and (SPAT; US-PGPUB; EFO; JPO; IBM_TDB USPAT; US-PGPUB; IBM_TDB USPA					
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"N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3)) 25 ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "B.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist) 216 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3) ((430/314,316,319-320,328-329).ccls. and (expos\$3) same (develop\$3)) ((430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (((430/314,316,319-320,328-329).ccls. and (nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) ("2922855").PN. EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB;		10			
Same (ash\$3 or etch\$3) IBM_TDB USPAT; US					
- 25 ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "B.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist) - 216 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3) - 211 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (expos\$3) same (develop\$3)) not ((430/314,316,319-320,328-329).ccls. and (heat\$3 or bak\$3) same (coxygen or "O.sub.2") same ((nitrogen or "N.sub.2")) same (ash\$3 or etch\$3)) and (heat\$3 or bak\$3) same (resist or photoresist)) - 3 ("2922855").PN. 2004/04/09 19:37 USPAT; US-PGPUB; EPO; JPO; IBM_TDB 2003/09/03 13:31 US-PGPUB; EPO; JPO; IBM_TDB 2003/09/03 13:52 USPAT; US-PGPUB; JPO;					
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"N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist) 216 430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3) 211 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (expos\$3) same (develop\$3)) not ((430/314,316,319-320,328-329).ccls. and (formula to the composition of th	}	23			. , =
Same (ash\$3 or etch\$3)) and (heat\$3 or bak\$3) same (resist or photoresist)					
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- 216 430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3) - 211 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (expos\$3) same (develop\$3)) not ((0xygen or "0.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3)) and (heat\$3 or bak\$3) same (resist or photoresist)) - 3 ("2922855").PN. USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; USPAT; US-PGPUB; JPO;				12.1_122	
(expos\$3) same (develop\$3) (expos\$3) same (develop\$3) (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (expos\$3) same (develop\$3)) not (coxygen or "0.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) ("2922855").PN. US-PGPUB; EPO; JPO; IBM_TDB EPO; JPO; IBM_TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; IS-PGPUB; IS-PGPUB; JPO;	1_	216		USPAT:	2003/03/10 17:38
EPO; JPO; IBM_TDB (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not ((430/314,316,319-320,328-329).ccls. and (oxygen or "0.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3)) and (heat\$3 or bak\$3) same (resist or photoresist)) ("2922855").PN. EPO; JPO; IBM_TDB US-PGPUB; US-PGPUB; JPO;		210			2000,00,20 2,000
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- 211 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not ((430/314,316,319-320,328-329).ccls. and (oxygen or "0.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) - 3 ("2922855").PN. USPAT; USPAT; USPAT; USPAT; USPAD; JPO;					
(expos\$3) same (develop\$3)) not ((430/314,316,319-320,328-329).ccls. and (oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) - 3 ("2922855").PN. US-PGPUB; US-PGPUB; JPO;		211	(130/328 cale and (heat\$3 or hak\$3) same		2003/09/03 13:31
(((430/314,316,319-320,328-329).ccls. and (coxygen or "O.sub.2") same ((nitrogen or "BM_TDB" "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) ("2922855").PN. USPAT; US-PGPUB; JPO;	-	211		,	2003/03/03 13:31
((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) - 3 ("2922855").PN. USPAT; US-PGPUB; JPO;				1	
"N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) USPAT; US-PGPUB; JPO;				1	
same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) - 3 ("2922855").PN. USPAT; US-PGPUB; JPO;				1 - 1 - 1 - 1 - 1 - 1	
bak\$3) same (resist or photoresist)) ("2922855").PN. USPAT; US-PGPUB; JPO;					
- 3 ("2922855").PN. USPAT; US-PGPUB; JPO; 2003/09/03 13:52					
US-PGPUB; JPO;	_	3 .		USPAT:	2003/09/03 13:52
JPO;			1 2022000 / 1211.		,, 10.02
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-	25	((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj	USPAT; US-PGPUB; EPO; JPO;	2004/04/09 19:30
		photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and	IBM_TDB	,
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		
		<pre>imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or</pre>		
		imag\$3 or pattern\$3))		
_	2	<pre>(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or</pre>	USPAT;	2004/04/09 19:29
	- X	magnetophotoresistive or (magneto adj	US-PGPUB; EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4	_	
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or</pre>		j
		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		<pre>photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3</pre>		
		or shrunk\$3 or contract\$3 or small\$3 or		
		<pre>littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same</pre>		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and		
		(polymethylglutarimide)		
_	54	(resist or photoresist) and	USPAT;	2004/04/09 19:28
		(napthoquinonediazide or napthoquinonediazido)	US-PGPUB; EPO; JPO;	
			IBM TDB	
-	3	((resist or photoresist) and	USPAT;	2004/04/09 19:28
		(napthoquinonediazide or napthoquinonediazido)) and (novolac or	US-PGPUB; EPO; JPO;	
		novolak) and dissolution near3 accelerat\$3	IBM_TDB	
-	32	((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or	USPAT;	2004/04/09 19:26
		"N.sub.2") and (hydrogen or "H.sub.2"))	US-PGPUB; EPO; JPO;	
		same (ash\$3 or etch\$3))) and (heat\$3 or	IBM_TDB	
		bak\$3) same (resist or photoresist)		

_	225	(430/328.ccls. and (heat\$3 or bak\$3) same	USPAT;	2004/04/09 19:19
		(expos\$3) same (develop\$3)) not	US-PGPUB;	
		(((430/314,316,319-320,328-329).ccls. and	EPO; JPO;	
		((oxygen or "O.sub.2") same ((nitrogen or	IBM TDB	
		"N.sub.2") and (hydrogen or "H.sub.2"))	_	
		same (ash\$3 or etch\$3))) and (heat\$3 or		
		bak\$3) same (resist or photoresist))		ľ
-	2	("5721078").PN.	USPAT;	2003/09/03 13:53
İ			US-PGPUB;	
			JPO;	
			DERWENT	